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DAINIPPON SCREEN MFG. CO., LTD.

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Dainippon Screen Announces the Single Bath Wet Station for Film Deposition Pre-Cleaning

Kyoto, Japan, November 27, 2003 ---- Dainippon Screen Mfg. Co., Ltd., (Headquarters: Kyoto; Japan / President: Akira Ishida) announces the release of its new 300mm single bath wet station for film advanced cleaning and surface preparation, the "F-ONE".

Wafer cleaning requirements are becoming increasingly stringent. Integrated circuit fabrication at the 65nm node mandates enhanced cleaning capability, process consistency, and strict interface integrity in a controlled ambient. The F-ONE addresses these challenges.

Base process technologies and mechanical systems for the F-ONE are derived from the FC-3000; the industry standard for 300mm wafer cleaning. Unlike the FC-3000, the F-ONE performs the entire cleaning and drying sequence in a single dry-in / dry-out chamber. This allows the F-ONE to maintain fundamental cleaning attributes (preventing cross-contamination, dilute chemical processing, watermark free drying, and metallic contamination control) with enhanced particle removal performance and interface control. The closed chamber design allows processing in a N2 environment to suppress native oxide growth.

By combining the entire process sequence into only one chamber, the F-ONE is substantially smaller than conventional wet stations. Its small footprint facilitates installation near downstream deposition equipment making time window management more feasible. Overall Cost-of-Ownership (CoO) reductions can be realized for many cleaning applications.

The F-ONE, the single bath wet station

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